

Design and Analysis of a 32×32 -bit SRAM

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Abstract—This work presents the design and system-level integration of a 32×32 -bit Static Random Access Memory (SRAM) module intended for FIFO-style read operations using a 5-bit address interface. The architecture comprises four primary components: a 5-bit adder for address computation, a 5-to-32 decoder for one-hot wordline selection, a 32×32 6T-cell SRAM array, and a differential sense amplifier for reliable data retrieval. The adder generates an effective address from two 5-bit inputs, which is subsequently decoded to activate a single wordline within the memory array. The selected row drives differential bitlines pre-loaded with data, and the sense amplifier resolves small bitline voltage differentials into full-swing digital outputs. Although write operations are excluded from the present scope, the design emphasizes correct read functionality, signal integrity, and robust interfacing between sub-blocks. This project provides a structured foundation for understanding SRAM read-path behavior and demonstrates the coordinated operation of modular VLSI memory components in a practical system.

Keywords—SRAM, 6T memory cell, decoder design, address adder; sense amplifier, static noise margin (SNM), write noise margin (WNM), bitline differential sensing, memory array architecture, VLSI design, FIFO addressing, digital integrated circuits.

I. INTRODUCTION

Static Random Access Memory (SRAM) forms a fundamental component of modern digital systems due to its high speed, low latency, and robust operational characteristics. As digital architectures increasingly rely on efficient on-chip memory structures, understanding the design and integration of SRAM subcomponents becomes essential. In this project, we develop a 32×32 -bit SRAM module accessed through a 5-bit address space, suitable for FIFO-style sequential memory operations. The design emphasizes accurate functionality, low read latency, and robust sensing of stored data while adhering to practical VLSI implementation constraints.

The SRAM system comprises four primary blocks: an address adder, a 5-to-32line decoder, a 32×32 6T-cell memory array, and a sense amplifier responsible for reliable output generation. In accordance with the design requirements, two 5-bit address inputs are first combined to form a single effective address. For this purpose, a **mirror adder architecture** is employed, offering reduced propagation delay and transistor symmetry favorable for high-speed and power-balanced arithmetic operations. The computed address is then decoded using a combinational decoder optimized for minimal wordline activation delay. The selected wordline enables exactly one of the 32 rows in the SRAM array,

connecting a 32-bit stored word to the corresponding differential bitlines.

During read operations, the differential nature of bitlines induces only small voltage deviations, necessitating an amplification stage to ensure correct logic-level interpretation. To address this, the design incorporates a **high-speed differential voltage sense amplifier**, which enhances sensitivity to small bitline differentials while maintaining fast decision time and low input-loading on the memory array. This amplifier ensures full-swing digital outputs even under minimal bitline voltage development, thereby improving both speed and robustness.

The overall system is evaluated through detailed simulation and characterization of the 6T SRAM cell, including static noise margin (SNM) and write noise margin (WNM) analysis, although write operations remain outside the scope of this project as per the given guidelines. Performance assessment includes critical-path delay analysis from the adder to the sense amplifier output, latency measurements, and the effect of design optimizations on system efficiency. This structured approach provides a comprehensive understanding of SRAM read-path behavior while highlighting the trade-offs inherent in high-speed memory design.

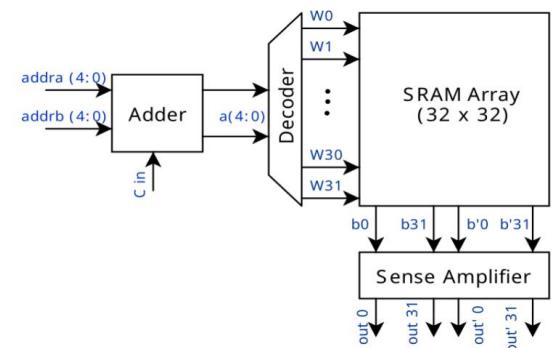


Figure: 32 x 32-bit SRAM Block Diagram

II. BLOCK-LEVEL DESIGN DESCRIPTION

A. ADDER

The adder in the SRAM read path is responsible for generating the effective 5-bit memory address by summing two 5-bit inputs along with an optional carry-in. Because this computation lies directly on the latency-critical path of the memory system, a high-speed arithmetic circuit is essential. For this purpose, a **mirror full adder** architecture is

employed. Mirror adders are commonly chosen in VLSI systems due to their symmetry, reduced transistor count, balanced rise/fall characteristics, and improved performance compared to conventional CMOS adders.

Function of the Adder:(for 1 bit)

$$\text{Sum} = A \oplus B \oplus \text{Cin}$$

$$\text{Cout} = AB + (A+B)\text{Cin}$$

The carry-out of each stage feeds the next higher-order bit, forming a 5-bit ripple chain that produces the complete address forwarded to the decoder.

Mirror Adder Structure:

The mirror adder consists of **complementary pull-up and pull-down transistor networks** arranged symmetrically, as shown in the provided diagram. It contains three key blocks per full-adder stage:

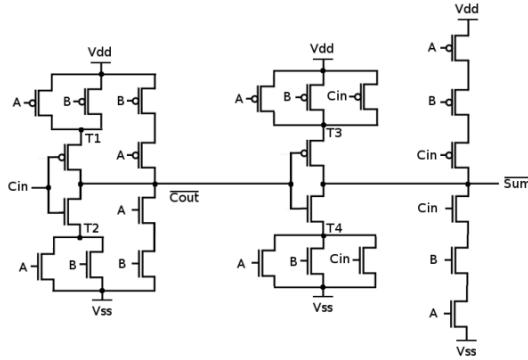


Figure: Mirror adder Implementation

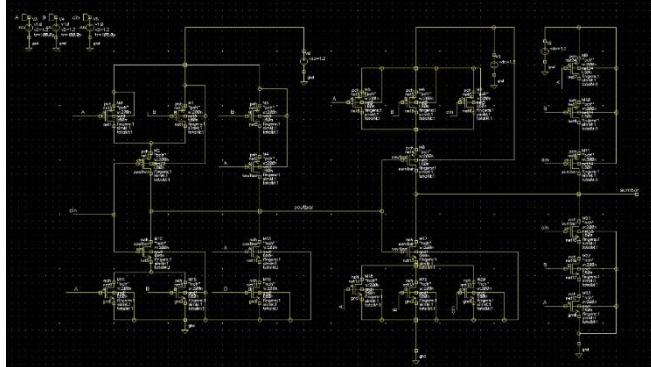


Figure: Mirror Adder in Cadence

1. Carry Generation Network (Cout Path)

This network evaluates the carry-out using stacked NMOS and PMOS transistors arranged to compute the majority function.

- The PMOS network (T1) pulls Cout high when two or more inputs are high.
- The NMOS network (T2) pulls Cout low under the corresponding complementary conditions.

Because the pull-up and pull-down structures exhibit mirror symmetry, both charging and discharging paths have nearly identical resistance, leading to:

- Reduced propagation delay
- Better noise margins
- Balanced switching behavior

The output of this network forms **Cout**, which is routed to the next stage.

2. Carry Propagation Between Stages

The generated **Cout** from one full-adder stage drives the **Cin** of the next stage.

This creates a **ripple-carry chain** across the 5 bits:

$$C_0 \rightarrow C_1 \rightarrow C_2 \rightarrow C_3 \rightarrow C_4$$

This interconnection ensures that the final 5-bit output correctly represents the sum of the two address inputs.

3. Sum Generation Network

The third block computes the **Sum output** using the previously computed carry signal. It evaluates:

$$\text{Sum} = (A \oplus B) \oplus \text{Cin}$$

The circuit uses a combination of PMOS/NMOS transmission-style XOR structures stacked vertically, as shown on the right side of the diagram. Key properties:

- Produces full-swing outputs
- Generates the sum after carry resolution
- Has small input loading due to symmetric transistor placement

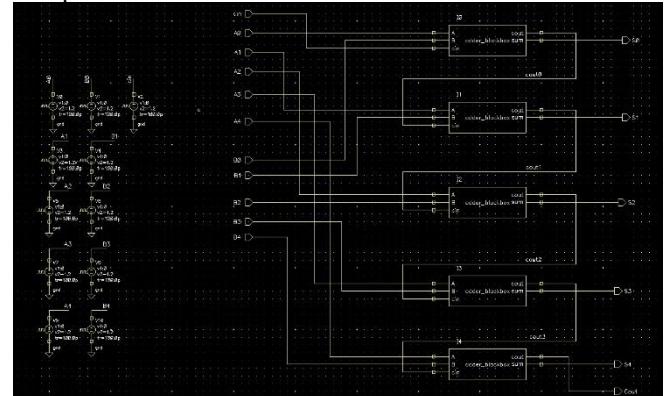


Figure: 5-bit Mirror Adder

Interconnection of Blocks:

Each full-adder stage comprises:

- A carry-generation block (left)
- A carry-propagation/mirror block (center)
- A sum-generation block (right)

The interconnections operate as follows:

1. **Inputs A and B** feed all three internal blocks (T1, T2, T3, T4).
2. **The carry-generation block** produces **Cout** based on A, B, and Cin.
3. **Cout** is passed to the carry network of the next full-adder stage.
4. The **Sum block** receives both (A,B) and the resolved carry signal to compute the final Sum for that bit.
5. This process repeats across five such stages to produce the effective 5-bit address.

The output of the fifth stage produces the final address signal, which is forwarded to the **5-to-32 decoder**.

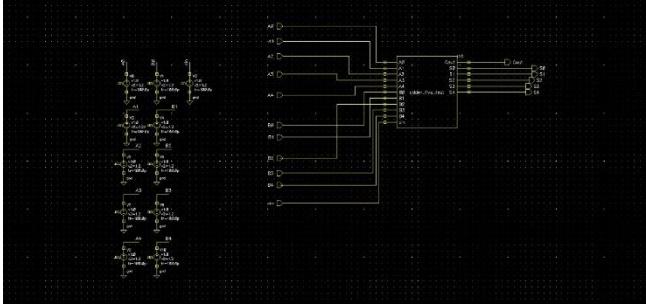


Figure: Final 5-bit Adder Block
Advantages of Using a Mirror Adder than CMOS:

A conventional CMOS full adder implements the sum and carry logic using separate pull-up and pull-down transistor networks for each Boolean expression. While this approach is functionally correct, it often results in higher transistor count, unbalanced rise/fall delays, increased load capacitances, and degraded speed on the critical carry chain. In contrast, the mirror adder is specifically optimized for high-speed arithmetic operations and offers several key advantages that make it more suitable for timing-critical memory systems such as the SRAM read path.

First, the mirror adder provides a **highly symmetric pull-up/pull-down structure**, ensuring that the carry-generation and carry-propagation paths exhibit nearly identical delay characteristics. This symmetry minimizes the difference between rising and falling transitions, resulting in **faster and more predictable propagation delays**, which is essential because the adder lies on the critical path of the SRAM address generation.

Second, the mirror adder achieves **lower transistor count and reduced internal node capacitances** compared to a full static CMOS logic implementation. The smaller capacitive load directly translates to shorter switching times, particularly for the carry-out signal that must ripple through all five stages of the 5-bit adder. This efficiency supports the overall objective of minimizing address computation latency.

Third, the mirror adder offers **superior drive capability for carry signals**, thanks to its dedicated transistor stacks for carry generation. Since the carry-out must be evaluated faster than the sum in multi-bit addition, the mirror structure naturally prioritizes this path, making it inherently more suitable for high-speed applications like SRAM decoding.

Finally, the mirror adder maintains **balanced power consumption and reduced logical effort** compared to CMOS adders, avoiding unnecessary transitions and minimizing dynamic power—a valuable property when used repeatedly across multiple address computations in memory subsystems.

B. DECODER

The decoder is an essential component of the SRAM read architecture, responsible for selecting exactly one of the 32 wordlines corresponding to the input address. It receives the 5-bit effective address generated by the adder and converts it into a **one-hot output**, ensuring that only a single row of the SRAM array is activated during a read operation. This one-hot behavior prevents conflicts on the bitlines and guarantees correct data retrieval.

Explanation of the 3-to-8 Decoder

The 3-to-8 decoder shown in the figure is a combinational logic circuit that converts a 3-bit binary input (A, B, C) into one of eight mutually exclusive outputs Y_0 to Y_7 . Only one output is asserted HIGH at any time, while the remaining outputs stay LOW. An additional enable signal E determines whether the decoder is active.

- **Inputs:**
- $A, B, C \rightarrow 3\text{-bit binary address}$
- $\bar{A}, \bar{B}, \bar{C} \rightarrow$ their inverted forms (generated using NOT gates)
- $E \rightarrow$ Enable signal
- **Outputs:**
- Y_0, Y_1, \dots, Y_7

Each output corresponds to one possible combination of the 3-bit input.

Function of the Decoder

The decoder implements the following logic:

$$Y_i = E \cdot f_i(A, B, C)$$

where f_i is the minterm corresponding to output Y_i .

For example:

- $Y_0 = E \cdot \bar{A}\bar{B}\bar{C}$
- $Y_1 = E \cdot \bar{A}\bar{B}C$
- $Y_2 = E \cdot \bar{A}BC$
- $Y_3 = E \cdot \bar{A}B\bar{C}$
- $Y_4 = E \cdot A\bar{B}\bar{C}$
- $Y_5 = E \cdot A\bar{B}C$
- $Y_6 = E \cdot AB\bar{C}$
- $Y_7 = E \cdot ABC$

Thus, only the output corresponding to the input combination is asserted HIGH.

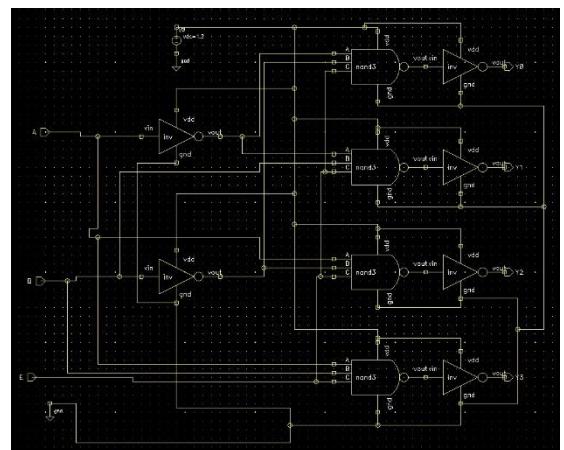


Figure: 2-4 Decoder Schematic

How the Circuit Works

1. Input Inversion

The signals **A**, **B**, **C** enter the NOT gates to generate their complements (\bar{A} , \bar{B} , \bar{C}).

These inverted signals are required because each output corresponds to a specific combination of true and complemented input bits.

2. AND Gates Generate Minterms

Each output Y_i is generated using a **3-input AND gate**. The AND gates receive a specific combination of:

- A or \bar{A}
- B or \bar{B}
- C or \bar{C}
- Enable signal E

By wiring the inputs in all possible minterm combinations, the circuit ensures **exactly one** output becomes 1 for any valid input.

Example:

- For $A = 0, B = 1, C = 0$:
 - $\bar{A} = 1, B = 1, \bar{C} = 1$
 - Only the AND gate generating Y_2 receives all 1s
 - So $Y_2 = 1$; all other outputs = 0

3. Enable Signal (E)

- When **E = 1**, the decoder works normally.
- When **E = 0**, all outputs are forced to **0**, regardless of A, B, C.

This is useful in hierarchical designs (like your 5-to-32 decoder) where only one block should be active at a time.

Function of the Decoder:

The 5-to-32 decoder takes a 5-bit binary address and produces 32 distinct outputs:

The primary function of the 5-to-32 decoder is:

Input: $(A_4, A_3, A_2, A_1, A_0) \rightarrow$ Output: $(W_0, W_1, \dots, W_{31})$

where

- Only **one** output (W_0 – W_{31}) is asserted HIGH at any time.
- The remaining **31 outputs** are held LOW.

This enables precisely one wordline in the SRAM array, allowing the 32 cells in that row to connect their stored data to the bitline pairs. An **enable (EN)** signal controls when the decoder is active; when EN is LOW, all wordlines remain disabled to allow safe bitline pre-charging between read cycles.

Decoder Design:

To achieve fast and power-efficient decoding, the design uses a **hierarchical structure** consisting of:

1. **One 2-to-4 pre-decoder**, which decodes the two most significant bits (MSBs)
2. **Four 3-to-8 decoders**, each responsible for decoding the three least significant bits (LSBs)

This hierarchical approach is preferred over a single large 5-input decoder because it reduces gate fan-in, minimizes propagation delay, lowers power consumption, and simplifies layout.

1. 2-to-4 Predecoder (MSB Decoding):

The predecoder receives the MSB pair (D, E) and generates four intermediate enable signals (D0–D3). Only one of these signals becomes HIGH based on the MSB value:

- MSB = 00 → D0 = 1
- MSB = 01 → D1 = 1
- MSB = 10 → D2 = 1
- MSB = 11 → D3 = 1

These four outputs act as **enable inputs** for the corresponding 3-to-8 decoders.

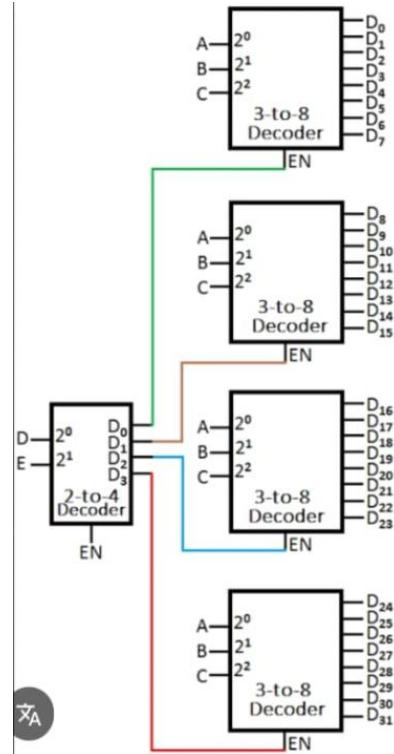


Figure: 5-32 decoder

2. Four 3-to-8 Decoders (LSB Decoding)

Each 3-to-8 decoder receives the same LSB group (A, B, C) but only one of them is enabled at a time. When enabled, the 3-to-8 decoder produces a one-hot output among its eight lines:

- Decoder 1 → W0–W7
- Decoder 2 → W8–W15
- Decoder 3 → W16–W23
- Decoder 4 → W24–W31

This modular structure ensures that the correct row is uniquely selected.

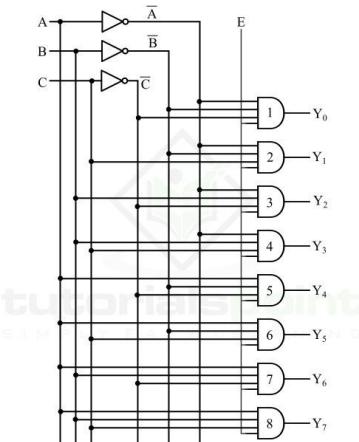


Figure 5 - 3 to 8 Decoder

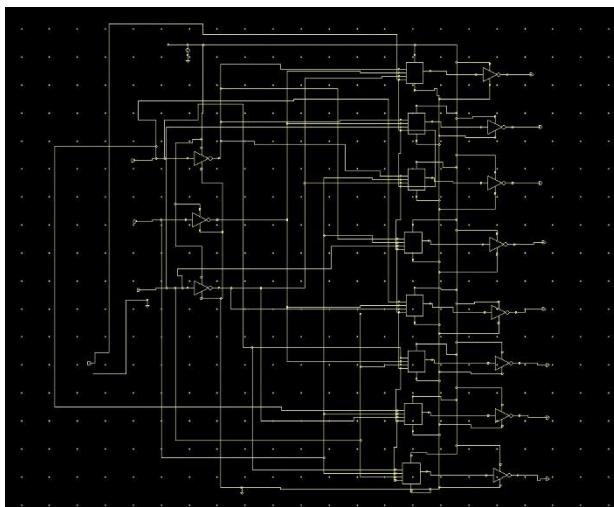


Figure: 3-8 Decoder schematic

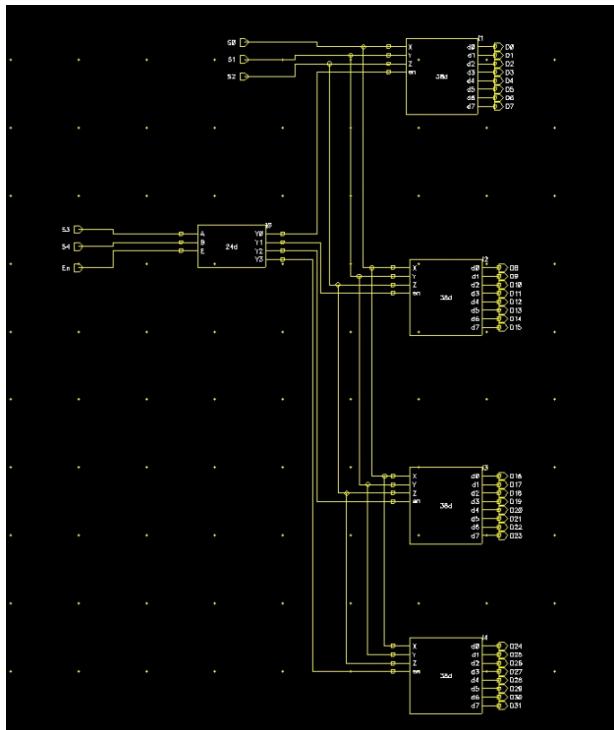


Figure: 5-32 Decoder schematic

Interconnection of Decoder Blocks:

The signals flow through the decoder in a structured manner:

1. The **adder output (5-bit address)** enters the decoder.
2. The **MSBs (D, E)** are routed to the 2-to-4 pre-decoder.
3. One of the four pre-decoder outputs enables exactly one 3-to-8 decoder.
4. The **LSBs (A, B, C)** are provided to all four 3-to-8 decoders.
5. Only the enabled 3-to-8 block generates the final wordline signal.
6. The resulting one-hot output (W0–W31) drives the corresponding wordline in the SRAM array.

This two-level hierarchical decoding ensures **low delay**, **reduced transistor count**, and **balanced power consumption**, making it highly suitable for memory architectures where decoding lies on a timing-critical path.

C. SRAM ARRAY

The SRAM array forms the core storage element of the memory system and is responsible for holding all the data that the decoder and sense amplifier operate upon. In this project, the memory array contains **32 rows × 32 columns**, where each storage element is implemented using a standard **6-transistor (6T) SRAM cell**. Each row corresponds to a 32-bit word, and each column corresponds to a single bit position across all words.

Function of the SRAM Array:

The SRAM array performs the following key functions:

1. Reliable Data Storage:

Each 6T SRAM cell stores one bit of data in the form of a stable bistable latch created by two cross-coupled inverters (T1–T4). The stored value is preserved as long as power is supplied.

2. Selective Row Access via Wordline:

The wordline (WL) determines which row is active.

When WL = 1 → access transistors (T5 and T6) turn ON and connect the cell to the bitlines.

When WL = 0 → the cell is electrically isolated and retains its data.

3. Bitline-Based Data Readout:

During a read operation, the selected row connects its internal storage nodes to the differential bitline pair (BL and BL̄).

Small voltage differences on the bitlines are then amplified by the sense amplifier to produce a full-swing digital output.

In this project the memory cells are preloaded using initial conditions, and **only the read operation is considered** (write operation is out of scope as per project guidelines).

6T SRAM Cell Design:

Each bit is implemented using a classical **6-transistor structure**, consisting of:

- **Two cross-coupled inverters:**
 - PMOS transistors: T2, T4
 - NMOS transistors: T1, T3

These maintain bistability and store either logic '0' or '1'.
- **Two NMOS access transistors (T5 and T6):**
Controlled by the wordline, these transistors connect the internal storage nodes to the bitline pair during read or write.

Important Roles of Transistors:

- **T1/T3 (NMOS)** and **T2/T4 (PMOS)** store the data value by forming a positive feedback loop.
- **T5 and T6** provide controlled access to the cell during read.
- **BL and \bar{BL}** act as data highways for all cells in the same column.

This arrangement enables fast, low-power memory operation with good noise margins.

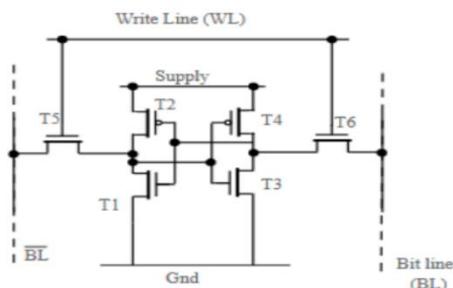


Figure 2: SRAM 6T cell

Array Organization and Block Design:

The 32×32 array is constructed by replicating the 6T cell layout in both the horizontal and vertical directions:

Rows (Wordlines):

- Each of the 32 rows is connected by a single wordline (WL0–WL31).
- The decoder drives exactly one wordline HIGH during a read operation.
- All 32 cells in the active row connect to their corresponding bitlines simultaneously, producing a 32-bit output word.

Columns (Bitlines):

- Each column has a differential bitline pair (BL, \bar{BL}).
- All cells in the same column share the same bitlines.
- The bitlines are precharged to VDD before every read cycle so that any small discharge caused by

the selected cell can be detected by the sense amplifier.

Cell Placement:

- Cells are arranged to minimize wiring, ensure symmetric layout, and reduce parasitic capacitance.
- The access transistors of adjacent cells are aligned for regularity and power efficiency.

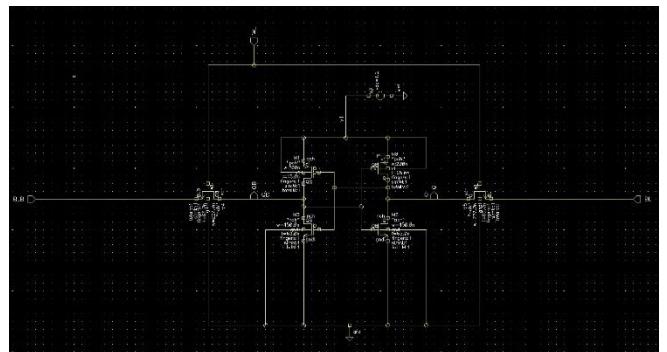


Figure: SRAM schematic

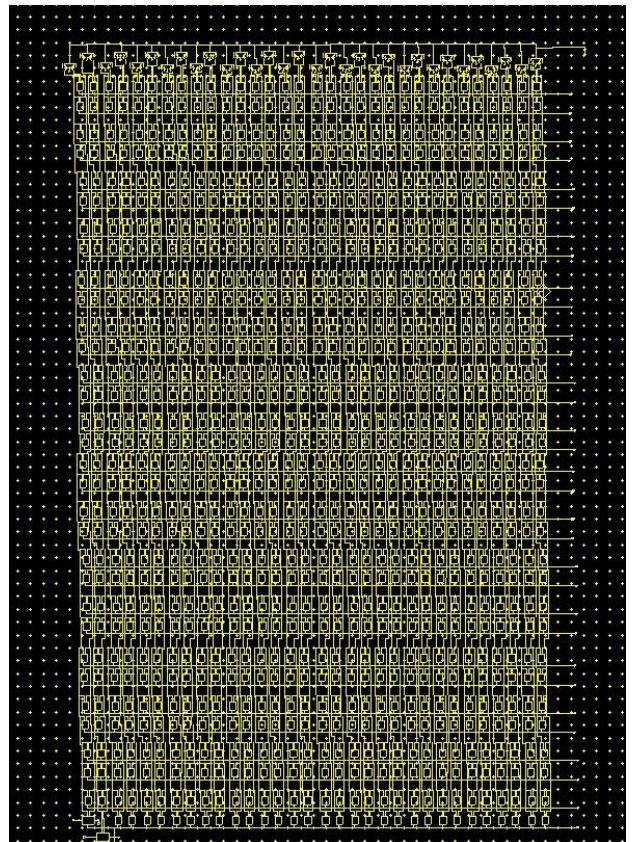


Figure: 32*32 SRAM

Interconnection With Other System Blocks:

1. Connection to Decoder

- The 5-to-32 decoder selects one wordline based on the address.

- Only the selected wordline turns ON the access transistors for that row.
- This ensures that only one row drives the bitlines.

2. Connection to Bitlines

- Each cell in a column connects its internal node to the shared bitline pair.
- Internal voltage difference created during a read is extremely small (tens of millivolts), so differential sensing is required.

3. Connection to Sense Amplifier

- After the bitline pair develops a small differential voltage, the sense amplifier amplifies it to full-swing logic (0 or 1).
- The sense amplifier reads all 32 columns in parallel, producing one 32-bit output word.

In summary, the SRAM array sits between the decoder (address selection) and the sense amplifier (data detection), acting as the central storage bank.

During a read operation, the differential voltage generated between the bit lines (BL and BL̄) is very small, typically in the range of a few millivolts. This small signal is insufficient for direct interpretation as a binary value (0 or 1). 2. Small voltage differences on bit lines are highly susceptible to noise, such as cross-talk from nearby circuits or fluctuations in the power supply. 3. A sense amplifier detects the small voltage difference between BL and BL̄ during a read operation and amplifies it to produce a full logic level (e.g., 0V for logic 0 or VDD for logic 1). 4. The differential architecture of sense amplifiers is inherently robust against common-mode noise, ensuring accurate data retrieval.

D. Sense Amplifier

The sense amplifier is a critical component in the SRAM read path, responsible for detecting and amplifying the extremely small voltage difference that develops on the differential bitline pair during a read operation. Since 6T SRAM cells cannot drive bitlines to full logic levels directly—especially when thousands of cells share the same bitlines—the sense amplifier ensures fast, reliable, and noise-immune data retrieval. In this design, a **high-speed differential voltage sense amplifier** is used to maximize read performance and minimize latency.

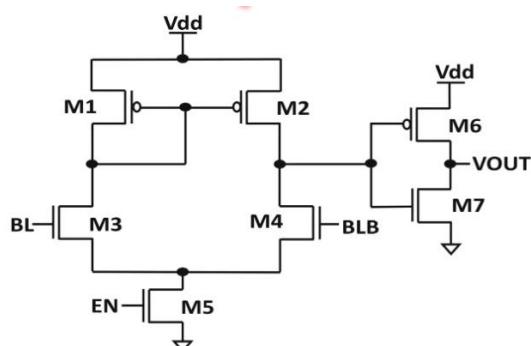


Figure: High Speed Differential Voltage Sense Amplifier

Function of the Sense Amplifier:

During a read operation:

1. **Pre-charge Phase:**
Both bitlines (BL and BL̄) are pre-charged to VDD.
2. **Bit-line Development:**
When a wordline is activated, the selected cell slightly discharges *one* of the bitlines depending on the stored value.
 - o Difference is typically **50–150 mV**, far too small for direct logic interpretation.
3. **Sensing Phase:**
The sense amplifier compares BL and BL̄ and amplifies the small voltage difference into a full-swing digital output (0 or 1).

Thus, the primary functions of the sense amplifier are:

- Detect minute differential voltage changes
- Amplify them to full-rail output
- Improve overall read-speed
- Reduce bitline loading and power consumption

Without a sense amplifier, SRAM read operations would be slow, power-hungry, and susceptible to noise.

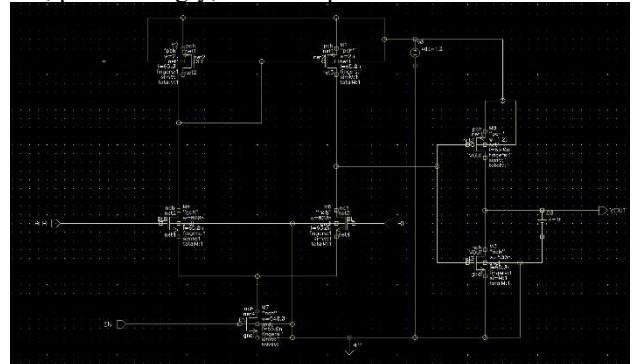


Figure: Sense Amplifier Schematic

Design of the Sense Amplifier:

A **differential voltage sense amplifier** is used for high-speed sensing. It generally consists of:

1. Differential Input Pair

The two inputs of the amplifier are connected to:

- BL (bitline)
- BL̄ (complementary bitline)

Even a small difference in these inputs causes a large switching effect due to high gain.

2. Cross-Coupled Inverter Latch

A pair of cross-coupled inverters forms a positive-feedback latch that:

- Rapidly regenerates the small initial difference
- Pushes the output to a stable logic 0 or logic 1
- Ensures fast and noise-tolerant operation

This regenerative behavior significantly improves sense speed.

• 3. Enable/Clock Signal

The amplifier is activated only after the bitline differential has developed sufficiently:

- Prevents incorrect sensing
- Reduces unnecessary power consumption

- Synchronizes sensing with the memory read cycle

Why Differential Sensing Is Used

- Higher noise immunity
- Faster voltage regeneration
- Smaller bitline swing → lower power
- Better matching and symmetry

This design choice aligns with the requirement for high-speed SRAM access.

Interconnection With the SRAM Array

The sense amplifier is situated **below each bitline pair** and interacts with other blocks as follows:

1. Connection to Bitlines

- Each amplifier receives BL and \bar{BL} from one column of the 32×32 array.
- Only the selected row's cell influences the bitline pair.
- The amplifier detects this change and produces a stable digital output.

2. Interaction With Wordline Activation

- Wordline enables one cell in the selected row.
- The cell slightly discharges one bitline; the other remains near VDD.
- The sense amplifier then senses and amplifies this difference.

3. Synchronization With Precharge Circuit

- Before each read cycle, bitlines are precharged to VDD.
- Sense amplifier stays disabled during precharge.
- Once precharge is complete and wordline is ON, sensing begins.

4. Output to the Digital Logic

- The amplifier outputs 32 bits corresponding to the selected memory row.
- These outputs are full-rail logic levels suitable for further digital processing.



Figure: 32 Sense Amplifiers

Advantages of the Differential Sense Amplifier

- **High speed:** Regenerative latch accelerates sensing.
- **Low power:** Requires only small bitline voltage swing.
- **High sensitivity:** Can detect voltage differences of <100 mV.
- **Noise immunity:** Differential architecture cancels common-mode noise.
- **Reduced area:** Simpler than dynamic amplifiers requiring large boosting circuits.

These benefits make it ideal for SRAM arrays where read delay directly impacts system performance.

III. SRAM CELL ANALYSIS

A standard 6-transistor SRAM cell is two cross-coupled inverters (a bistable latch) and two NMOS access devices. The nodes are Q and QB, bitlines are BL and BLB, and WL is the wordline. The six transistors are typically named:

- Pull-up PMOS devices (PU): M0, M1

- Pull-down NMOS devices (PD): M2, M3
- Access NMOS devices (ACC): M4, M5

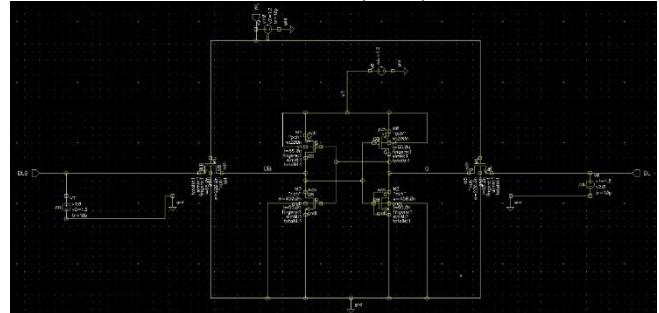


Figure: 6T SRAM Cell Schematic

A. Purpose of each transistor (functional role)

- **M0 / M1 — Pull-up (PU) PMOS (connected VDD → storage node):**

Keep the '1' storage node pulled to VDD when the cell holds logic '1'. They provide the weak restoring current for the high node and form the top halves of the cross-coupled inverters.

- **M2 / M3 — Pull-down (PD) NMOS (storage node → GND):**

Hold the '0' node strongly at ground when the cell stores logic '0'. These devices determine how strongly a node resists being pulled up during a read.

- **M4 / M5 — Access (ACC) NMOS (BL ↔ storage node when WL = 1):**

Connect the internal node to the bitline during read/write. During read they allow the precharged BL/BLB to sense the stored bit (but must be weak enough to avoid flipping the cell). During write they must be strong enough to allow the bitline driver to override the existing stored state.

1. Access Transistors

The access transistors are NMOS devices that control the connection between the bitlines and the internal storage nodes. Their gates are connected to the wordline (WL).

During Hold State (WL = 0):

- Both M4 and M5 are OFF, completely isolating the storage nodes (Q, QB) from the bitlines (BL, BLB).
- The cell retains its stored data through the cross-coupled inverters with no external interference.

During Read Operation (WL = 1):

- M4 and M5 turn ON, creating conducting paths between the storage nodes and the pre-charged bitlines.
- Depending on the stored data, one of the bitlines begins to discharge through its access transistor and the corresponding pull-down transistor.
- A small voltage differential (typically 100-200mV) develops between BL and BLB, which is then sensed and amplified by the sense amplifier.
- Critical constraint: The access transistors must be sized weak enough to prevent read disturb – they should not pull the '0' storage node above the inverter trip point, which would flip the cell contents.

During Write Operation (WL = 1):

- M4 and M5 turn ON, allowing the bitline drivers to force new values onto the storage nodes.

- To write a ‘0’ to Q (previously storing ‘1’), BL is driven to 0V while BLB is driven to VDD.
- The access transistor M1, in combination with the external driver, must be strong enough to overpower the pull-up transistor M3 and pull Q below the inverter threshold.
- Once Q drops sufficiently, the positive feedback through the cross-coupled inverters completes the write operation.

2. Pull-up Transistors

The PMOS transistors M3 and M4 serve as the pull-up (load) devices in the cross-coupled inverters, connected between VDD and the storage nodes.

During Hold State:

- When Q = 0, QB = 1, causing M3 to be ON (gate at 1) and M4 to be OFF (gate at 0).
- M0 maintains QB at VDD, while M5 maintains Q at GND.
- The opposite configuration occurs when the cell stores the complementary state.

During Read Operation:

- The pull-up transistors maintain their states, providing weak restoration current to the storage nodes.
- They are intentionally sized smaller than the pull-down transistors to ensure read stability.
- The ratio between pull-down strength and pull-up strength directly affects the Static Noise Margin (SNM).

During Write Operation:

- The pull-up transistor opposing the write must be overpowered by the access transistor and bitline driver.
- For example, to write ‘0’ to Q, M0 must be overpowered to allow Q to be pulled below the trip point.
- Smaller pull-up transistors facilitate easier writes (higher Write Noise Margin) but may reduce read stability.

3. Pull Down Transistors

The NMOS transistors M2 and M3 form the pull-down network of the cross-coupled inverters, connected between the storage nodes and GND.

During Hold State:

- When Q = 1, QB = 0, M3 is ON (gate at 1) and maintains QB at GND.
- Conversely, M2 is OFF since its gate is connected to QB (at 0).
- These transistors ensure that the ‘0’ node remains firmly at ground potential.

During Read Operation:

- The pull-down transistor connected to the ‘0’ storage node plays a critical role in read stability.
- For instance, if Q = 0 and QB = 1, when the wordline activates, M1 creates a path from BL to Q.
- M5 must be strong enough to sink the current from M1 without allowing Q to rise above the inverter trip point.

During Write Operation:

- Once the opposing pull-up is overpowered and the storage node begins to transition, the pull-down transistor assists in completing the write.
- For example, when writing ‘0’ to Q, once Q drops below the trip point, QB begins to rise, turning on M2, which further pulls Q to ground.
- Strong pull-down transistors ensure fast and complete write operations.

B. Transistor Sizing and Design Trade-offs

W/L Ratio Selection Criteria:

The typical design hierarchy for transistor strengths is:

$$\beta_{\text{pull-down}} > \beta_{\text{access}} > \beta_{\text{pull-up}}$$

This sizing strategy can be quantified using two key ratios:

Cell Ratio (CR): $\text{CR} = \beta_{\text{pull-down}} / \beta_{\text{access}}$

Typically, $\text{CR} = 1.5 - 2.5$.

- $\text{CR} < 1.3$: High risk of read disturb (storage node rises too much during read)
- $\text{CR} > 2.5$: Write margin collapses and area increases
- During write, you want the access transistor to overpower the inverter and change its state.
- If the pull-down is too strong (big CR), the access device cannot pull the internal node high/low enough → write failure.
- Also, bigger pull-down = bigger transistor → more area, more bitline capacitance, more power

Write Ratio (WR):

$$\text{WR} = \beta_{\text{access}} / \beta_{\text{pull-up}}$$

Typically, $\text{WR} > 1$ but < 1.6 .

- $\text{WR} < 1$: PMOS too strong → write failures (cell cannot flip)
- $\text{WR} > 1.6$: Access transistor too strong → read stability issues

The sweet spot around $\text{CR} = 2.0$ and $\text{WR} = 1.5$ ensures both read stability and writability across process corners.

- BL is driven to 0, WL = 1 → access NMOS connects BL to node Q.
- The access transistor must pull node Q down through the pull-up PMOS that is still trying to hold Q at VDD
- If access current > PMOS current for long enough, node crosses the inverter switching threshold and the internal latch flips.
- The access transistor (connected to the bitline) tries to pull the node down to 0.
- The PMOS pull-up (inside the inverter) tries to keep the node at 1 (VDD).
- So, access nmos must be stronger than pmos

$$\text{WR} > 1$$

If WR is too low (1.6) → access transistor too strong → might disturb the cell during read or waste area/power.

1. W/L calculations:

Method 1:

The primary design objectives were to achieve a Static Noise Margin (SNM) and Write Noise Margin (WNM) greater than 200mV. The design uses principles of the Cell Ratio (CR) for read stability and the Pull-Up Ratio (WR) for write-ability.

The final design resulted in transistor widths of

450nm for the Pull-Down (PD),

220nm for the Access (ACC),
200nm for the Pull-Up (PU) devices.

The design is constrained by the following specifications-

- Technology: 65 nm, Supply Voltage (VDD): 1.0 V
- Stability Metrics- Static Noise Margin (SNM) ≥ 200 mV, Write Noise Margin (WNM) > 200 mV

To meet these stability specifications, the internal design targets were:

Cell Ratio (CR): 2.0 (for read stability)

Pull-Up Ratio (WR): 1.1 (for write-ability).

Design Methodology:

The strength of a transistor (β), is proportional to its Width-to-Length ratio (W/L). The procedure begins with the foundational Pull-Down transistors and sequentially sizes the Access and Pull-Up transistors based on the target ratios.

Sizing the Pull-Down NMOS (PD1, PD2)-

The Pull-Down NMOS transistors form the core of the cross-coupled inverter latch. They must be strong enough to reliably maintain the stored state. A common design rule of thumb is to set the PD width as a multiple (k) of the minimum channel length (L) to ensure high current drive. A value of k=6-8 is typical.

Calculation - Selected k = 7.

Initial $W_{PD} = k \times L = 7 \times 65\text{nm} = 455\text{nm}$

The pull-down NMOS transistors (M5, M6) were sized using a width multiplier of k = 7 relative to the minimum channel length (L = 65 nm), resulting in a width of $W_{PD} = 455$ nm (rounded to 450 nm).

This value was selected based on the following considerations

1. Current Drive Requirement: A multiplier of k = 7 ensures sufficient saturation current to maintain state stability during read operations and provide robust feedback in the cross-coupled inverter pair.

2. Optimal Cell Ratios: This sizing yields a Cell Ratio (CR = $\beta_{\text{pull-down}} / \beta_{\text{access}}$) of approximately 2.07, which falls within the recommended range of 1.8–2.5 for balancing read stability and writeability.

3. Layout Efficiency: A width of $\sim 7 \times L$ offers a compact transistor layout, facilitating efficient contact placement and routing while minimizing overall SRAM cell area.

4. Process Considerations: The value aligns with industry practices for 65 nm technology, providing a robust design that accommodates process variations without excessive area penalty.

The value was adjusted to $W_{PD} = 450\text{nm}$ for the schematic to match the manufacturing grid, simplifying the layout process without a significant performance penalty.

Sizing the Access NMOS (ACC1, ACC2)

This is from Cell Ratio (CR)- The Access transistors must be sized relative to the Pull-Down devices to ensure read stability. A sufficiently high CR prevents the cell from flipping during a read operation.

The Cell Ratio is defined as

$$CR = \beta_{PD}/\beta_{ACC}.$$

Assuming identical lengths, this simplifies to

$$CR \approx W_{PD}/W_{ACC}.$$

Calculation-

$$W_{ACC} = W_{PD}/CR = 450\text{nm}/2.0 = 225\text{nm}.$$

The calculated width was slightly adjusted to

$$W_{ACC} = 220\text{nm}. \text{ This minor increase provides an additional margin for read stability. } CR = 450\text{nm}/220\text{nm} = 2.045.$$

Sizing the Pull-Up PMOS (PU1, PU2)

This is from Pull-Up Ratio (WR)- The Pull-Up PMOS transistors are sized to allow the cell to be written to reliably. A lower WR makes it easier for the Access transistors to overpower the Pull-Up devices during a write cycle.

The Pull-Up Ratio is defined as $WR = \beta_{ACC}/\beta_{PU}$. Assuming identical lengths, this simplifies to $WR \approx W_{ACC}/W_{PU}$. Calculation: $W_{PU} = W_{ACC}/WR = 220\text{nm}/1.1 = 200\text{nm}$. $WR = 220\text{nm}/200\text{nm} = 1.10$. This confirms the target was met exactly.

Verification:

The final design was verified through analytical and simulation-based methods.

• **Analytical Verification:** The transistor currents during critical read and write operations were analyzed using the square-law saturation current equation,

$$ID = (\frac{1}{2}) * \beta(VGS - VTH)^2.$$

This analysis confirmed that the voltage at the internal storage node (V_Q) is not excessively degraded during a read and can be robustly pulled down during a write.

• **Simulation Verification:** The design was simulated using industry-standard EDA tools. Post-layout simulations confirmed that the final transistor sizing successfully meets the primary specifications of SNM $> 200\text{mV}$ and WNM $> 200\text{mV}$.

The optimized transistor dimensions for the 65nm 6T SRAM cell are presented below.

Transistor	Type	Width	Length
Pull-Down (PD1, PD2)	NMOS	450 nm	65 nm
Access (ACC1, ACC2)	NMOS	220 nm	65 nm
Pull-Up (PU1, PU2)	PMOS	200 nm	65 nm

Achieved Performance Metrics:

- Cell Ratio (CR): 2.045
- Pull-Up Ratio (WR): 1.10

Method 2:

Current Relationships for Stable Operation

During READ (worst-case stability)- The pull-down NMOS must be stronger than the access transistor. Condition is $I_{pull-down} > I_{access}$ when storage node is rising

During WRITE (worst-case writability) -The access transistor must be stronger than the pull-up PMOS. Condition is $I_{access} > I_{pull-up}$ when flipping the cell

Let's use typical 65nm parameters:

- VDD = 1.0V
- VTH,N = 0.25V (NMOS threshold voltage)
- VTH,P = -0.25V (PMOS threshold voltage)
- $\mu_n C_{ox} = 270 \mu\text{A/V}^2$ (NMOS transconductance)
- $\mu_p C_{ox} = 70 \mu\text{A/V}^2$ (PMOS transconductance) - PMOS is much weaker!
- L = 65nm (minimum length)

READ Stability Analysis

Worst-Case READ Scenario

- Stored data: Q=0, QB=1, WL=1, BL=BLB=precharged to VDD, Critical node: Q starts rising due to current through M1

Current Equations (Saturation):

Access transistor M1 current:

$$I_{access} = \frac{1}{2} \mu_n C_{ox} \frac{W_{access}}{L} (V_{GS} - V_{TH})^2$$

At the critical point when Q is rising:

$$\begin{aligned} V_{GS,M1} &= V_{WL} - V_Q \approx 1.0 - V_Q \\ I_{access} &= \frac{1}{2} \times 270 \times \frac{W_{access}}{65} (0.75 - V_Q)^2 \end{aligned}$$

Pull-down transistor M5 current:

$$I_{pull-down} = \frac{1}{2} \times 270 \times \frac{W_{pull-down}}{65} (1.0 - 0.25)^2$$

Read Stability Condition:

For stability, we need $I_{pull-down} > I_{access}$ at the inverter trip point ($V_Q \approx 0.4V$):

$$\frac{1}{2} \times 270 \times \frac{W_{pd}}{65} \times (0.75)^2 > \frac{1}{2} \times 270 \times \frac{W_{access}}{65} \times (0.6)^2$$

$$\frac{W_{pd}}{W_{access}} > \frac{0.36}{0.5625} \approx 0.64$$

This seems too small, so let's be more conservative and consider the current ratio:

$$\frac{I_{pull-down}}{I_{access}} = \frac{W_{pd}}{W_{access}} \times \frac{(0.75)^2}{(0.6)^2} = \frac{W_{pd}}{W_{access}} \times 1.5625$$

For good read stability, we want this ratio > 2.0:

$$\begin{aligned} \frac{W_{pd}}{W_{access}} \times 1.5625 &> 2.0 \\ \frac{W_{pd}}{W_{access}} &> 1.28 \end{aligned}$$

Let's choose $W_{pd} / W_{access} = 2.0$ for robust stability

WRITE Ability Analysis

Worst-Case WRITE Scenario- Writing '0' to Q (Q was 1, QB was 0), WL=1, BL=0V, BLB=VDD, M1 must pull Q down against M3

Access transistor M1 current (when Q ≈ VDD):

$$I_{access} = \frac{1}{2} \times 270 \times \frac{W_{access}}{65} \times (1.0 - 0.25)^2$$

Pull-up transistor M3 current (when Q dropping):

$$\begin{aligned} I_{pull-up} &= \frac{1}{2} \mu_p C_{ox} \frac{W_{pull-up}}{L} (|V_{GS}| - |V_{TH}|)^2 \\ I_{pull-up} &= \frac{1}{2} \times 70 \times \frac{W_{pu}}{65} \times (1.0 - 0.25)^2 \end{aligned}$$

Write Ability Condition:

For successful write: $I_{access} > I_{pull-up}$

$$\frac{1}{2} \times 270 \times \frac{W_{access}}{65} \times 0.5625 > \frac{1}{2} \times 70 \times \frac{W_{pu}}{65} \times 0.5625$$

$$\frac{W_{access}}{W_{pu}} > \frac{70}{270} \approx 0.26$$

But again, let's be more conservative and consider we want strong write ability:

$$\frac{I_{access}}{I_{pull-up}} = \frac{270 \times W_{access}}{70 \times W_{pu}} = 3.857 \times \frac{W_{access}}{W_{pu}}$$

For good write ability, we want this ratio > 1.5:

$$\frac{3.857 \times \frac{W_{access}}{W_{pu}}}{W_{access}} > 1.5$$

$$\frac{W_{access}}{W_{pu}} > 0.39$$

Let's choose $\frac{W_{access}}{W_{pu}} = 1.1$ for strong write ability

We now have

$$1. W_{pd} / W_{access} = 2.0 \text{ (from read stability)}$$

$$2. W_{access} / W_{pu} = 1.1 \text{ (from write ability)}$$

Let's start with a reasonable access transistor size. In 65nm, a common starting point is 1.5-2× minimum width. Minimum width might be ~120nm, so: Choose $W_{access} = 220\text{nm}$. From equation 1: $W_{pd} = 2.0 \times 220 = 440\text{nm} \rightarrow$ round to 450nm. From equation 2: $W_{pu} = 220 \times 1.1 = 242\text{nm}$

Verification with Current Calculations-

Let's verify these sizes give the desired current ratios.

READ Stability Check:

$$\frac{I_{pull-down}}{I_{access}} = \frac{450}{220} \times \frac{(0.75)^2}{(0.6)^2} = 2.045 \times 1.5625 \approx 3.19$$

Ratio > 3.0 provides robust read stability

WRITE Ability Check:

$$\frac{I_{access}}{I_{pull-up}} = \frac{270 \times 220}{70 \times 242} = \frac{59400}{14000} \approx 4.24$$

Ratio > 4.0 provides strong write ability

Read Stability: Pull-down is 2x wider than access transistors, providing 3.19× current advantage at the critical trip point

Write Ability: Access transistors are 1.1x wider than pull-ups, but due to mobility advantage ($\mu_n/\mu_p \approx 3.86$), they have 4.24× current advantage

Balance: The design satisfies both conflicting requirements simultaneously

2. Design Trade-offs:

Read Stability vs. Write-ability:

- Read stability is quantified by the Static Noise Margin (SNM), which improves with stronger pull-downs and weaker access transistors.
- Write-ability is quantified by the Write Noise Margin (WNM), which improves with stronger access transistors and weaker pull-ups.
- These requirements are fundamentally in opposition, necessitating a balanced design approach.

Cell Area vs. Performance:

- Larger transistors improve noise margins and switching speed but increase cell area, reducing memory density.
- Minimum-sized transistors minimize area but may result in marginal stability, especially under process variations and voltage/temperature fluctuations.

Power Consumption:

- Larger transistors increase parasitic capacitances on the storage nodes and bitlines, leading to higher dynamic power during reads and writes.
- Subthreshold leakage increases with transistor width, affecting standby power consumption

C. Working of SRAM

Applied transient analysis to the SRAM 6T to verify its working

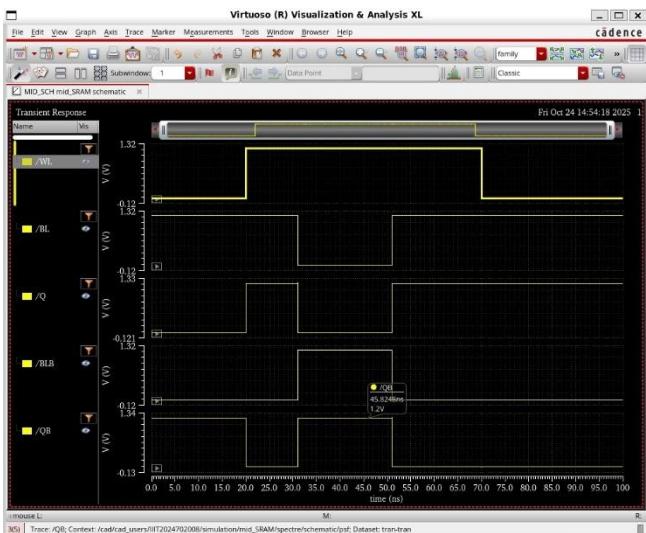


Figure: Transient Analysis

When Word Line is 1, Q follows BL and QB follows BLB. Working is verified

Read (WL = 1; BL/BLB pre-charged)

1. BL and BLB pre-charged to VDD; WL asserted \rightarrow ACC devices turn ON.
2. If cell stores $Q = 0$, $QB = 1$: the BL connected to Q will begin to discharge through ACC and the PD transistor that holds the 0, producing a small differential between BL and BLB.
3. Sense amplifier detects the small differential (typically a few 100 mV) and amplifies it to full rail. **Key constraint:** the ACC must be weak enough relative to PD that the '0' node does not rise past the inverter trip point (read disturb). This motivates a relatively high CR.

Write (WL = 1; BL driven to target values)

1. To write a '0' to Q: $BL = 0V$, $BLB = VDD$, $WL = 1 \rightarrow$ ACC connects BL to Q.
2. The ACC + external bitline driver must pull Q below inverter switching threshold despite the PU trying to keep $Q = 1$.
3. Once Q crosses the trip point, positive feedback of cross-coupled inverters completes the flip. **Key constraint:** ACC and driver must be strong enough vs PU \rightarrow motivates $WR > 1$ (PU relatively weak).

D. Static Read Noise Margin (SNM) Analysis

The Static Noise Margin (SNM) quantifies the SRAM cell's robustness against noise during a read operation. It represents

the maximum DC noise voltage that can be tolerated at the storage nodes before the cell loses its stored data.

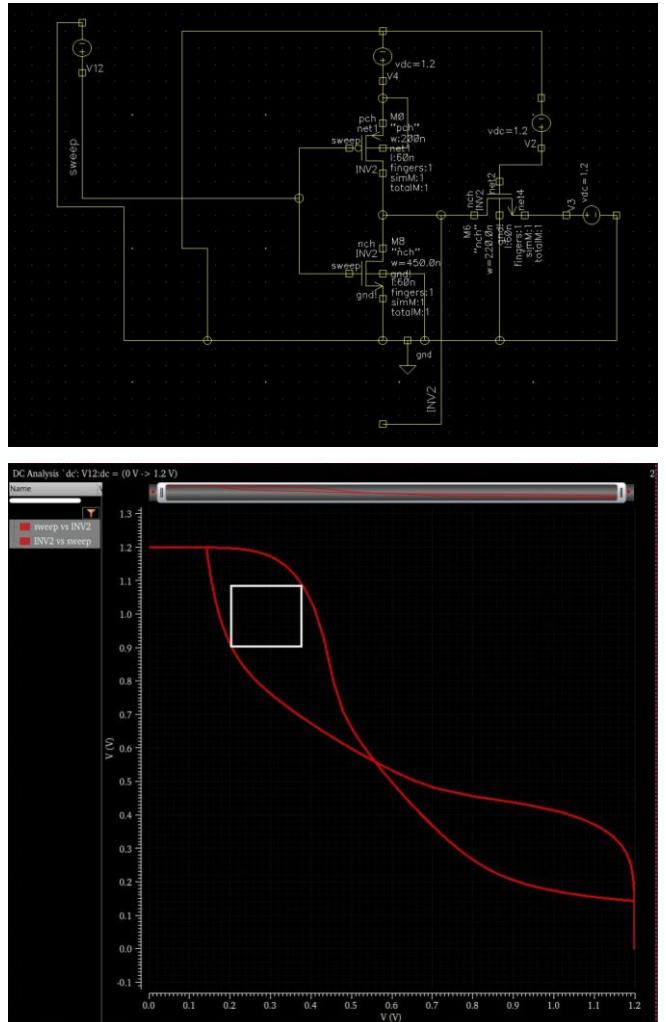


Figure: Read operation waveform of 6T SRAM cell showing bitline precharge, differential development, and sense amplifier output

The **SNM of the SRAM is 190mV** (length of side of the max possible square)

Worst-case voltage rise in the SRAM cell during a read (i.e., the value of $V2$ when $V1$ is at VDD) is **142mV** as seen from the plot below.

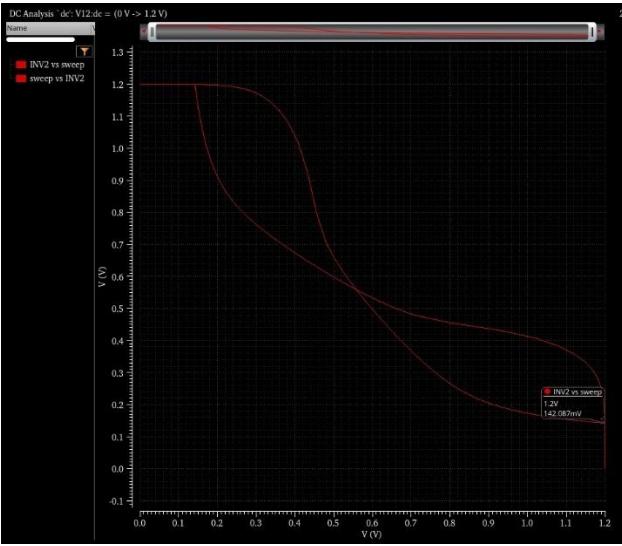


Figure: Worst case cell voltage

SNM Extraction Methodology:

The SNM is extracted using the "butterfly curve" method, which involves the following steps:

1. Break Feedback Loop:

The positive feedback in the cross-coupled inverters is broken by disconnecting one inverter's output from the other's input.

2. Simulate VTC:

Perform a DC sweep of node V1 from 0V to VDD while measuring V2:

- First VTC: Sweep V1 (input of Inverter 1), measure V2 (output of Inverter 1)
- This gives the forward VTC: $V_2 = f(V_1)$

3. Create Inverse VTC:

Plot the inverse characteristic by swapping axes:

- Second VTC: Plot V1 vs. V2, which is equivalent to the VTC of Inverter 2

4. Overlay VTCs:

Superimpose both VTCs on the same plot to create the butterfly curve.

5. Find Maximum Square:

The SNM is defined as the side length of the largest square that can be inscribed within each lobe of the butterfly plot.

Interpretation:

- The worst-case $V_{2,\max} = 142 \text{ mV}$ is well below typical inverter trip ($\sim 0.4 \text{ V}$) — read disturb is limited, but SNM is slightly below the "recommended good" threshold. If you must operate at reduced VDD, SNM will degrade and may require stronger PD or read-assist.
- For $VDD = 1.0\text{--}1.2 \text{ V}$, an SNM of 190 mV corresponds to $\sim 0.16\text{--}0.19 \times VDD$ (if $VDD = 1.2 \text{ V}$, $190 \text{ mV} \approx 0.158 \times VDD$). Industry rules of thumb reported: minimum acceptable SNM $\approx 0.2 \times VDD$ is marginal, $>0.3 \times VDD$ is good. So this cell lies around

marginal/good depending on the VDD assumed in the plot (report uses 1.2 V in some WNM runs).

Design implications and fixes if SNM is low:

- Increase PD width (raise CR) or reduce ACC width, at cost of writeability or area/power.
- Use read-assist techniques (wordline underdrive, bitline biasing) for low-V operation.

E. Write Noise Margin(WNM) Analysis

The Write Noise Margin (WNM) quantifies the ease with which the SRAM cell can be written. It represents the minimum voltage required to successfully flip the cell state during a write operation.

WNM Extraction Methodology:

Similar to SNM extraction, WNM uses the butterfly curve method but under write conditions:

1. Setup Write Conditions:

- Wordline (WL) = VDD (access transistors on)
- One bitline driven to 0V, other to VDD (e.g., BL = 0V, BLB = VDD)

2. Break Feedback Loop:

Disconnect the cross-coupled inverter feedback.

3. Simulate Asymmetric VTCs:

Unlike SNM, the two half-cells now have different VTCs due to different bitline voltages:

- VTC 1: Half-cell connected to BL = 0V
- VTC 2: Half-cell connected to BLB = VDD

4. Create Butterfly Plot:

Overlay the two asymmetric VTCs.

5. Find Maximum Square:

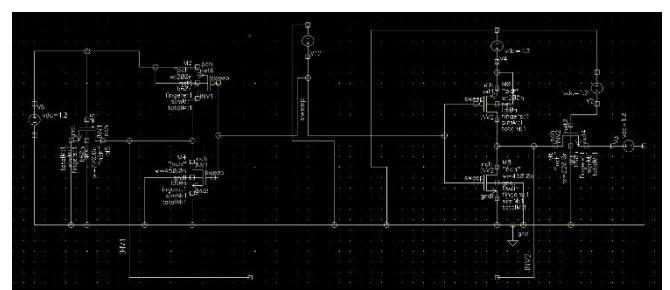
The WNM is the side length of the largest square inscribed in the smaller lobe of the butterfly plot.

Simulation Setup Circuit Configuration:

- Wordline (WL) = VDD
- Bitline (BL) = 0V (writing '0')
- Bitline (BLB) = VDD (writing '1')
- Supply voltage: VDD = 1.2 V
- Temperature: 27°C

DC Sweep Parameters:

- Sweep variable: V1 or V2 (depending on configuration)
- Sweep range: 0V to VDD
- Step size: 1–10mV



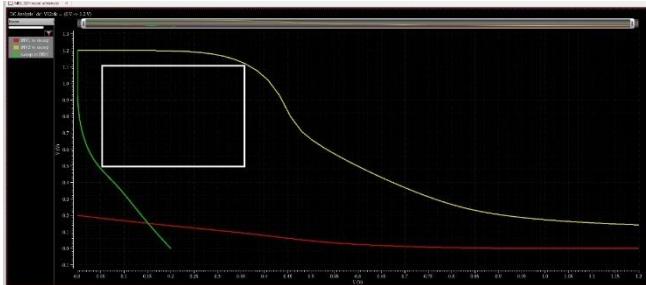


Figure: Write Noise Margin analysis results

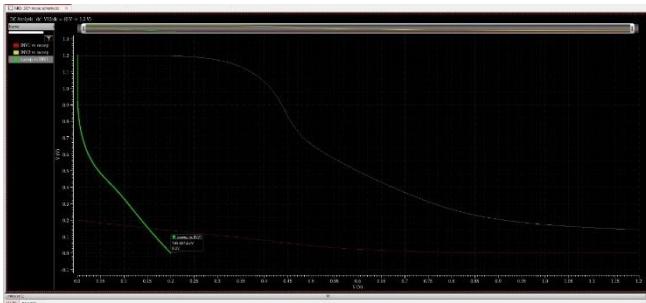


Figure: Worst case cell voltage

The **WNM is 600mV** The worst-case cell voltage during a write (which is found from measuring V1 when V2 is at 0V) is **200mV**

Worst-Case Cell Voltage During Write:

The critical parameter for write-ability is the voltage at node V1 when the opposite node V2 is forced to 0V:

$$V_{1,max} = 200 \text{ mV, when } V2 = 0\text{V}$$

For a successful write, this voltage must be pulled below the inverter trip point by the access transistor and bitline driver:

$$V_{1,max} < V_{th,inv} \approx \frac{V_{DD}}{2} \quad (13)$$

Analysis:

- If $V_{1,max} < 0.4 \times V_{DD}$: Excellent write-ability
- If $0.4 \times V_{DD} < V_{1,max} < 0.5 \times V_{DD}$: Acceptable write margin
- If $V_{1,max} > 0.5 \times V_{DD}$: Difficult to write; may require stronger access transistors or write-assist techniques

Interpretation:

- WNM = 600 mV is large and indicates **excellent**
- **Write ability**; the access transistor and bitline driver comfortably overpower the pull-up during writes. For $V_{DD} = 1.2 \text{ V}$, $600 \text{ mV} \approx 0.5 \times V_{DD}$ — well above minimum industry thresholds ($>0.2 \times V_{DD}$ as marginal, $>0.25 \times V_{DD}$ recommended).
- $V_{1,max} = 200 \text{ mV}$ is below common inverter trip thresholds, so writing is robust.

Design trade-offs: increasing ACC to raise WNM degrades SNM (read stability), so the chosen point (ACC 220 nm, PU 200 nm, PD 450 nm) achieves the intended balance.

IV. CRITICAL PATH ANALYSIS

Timing analysis was performed to characterize the latency of individual blocks along the critical path. As and Bs are all 1s. That's when we have the critical path. All the carry's must be 1. The carry must ripple through every single bit to produce the final sum and carry out. This is the longest time it takes to reach output from Vin. Because this input combination forces the worst-case carry propagation chain, meaning: Each stage generates or propagates a carry. The carry must ripple through every single bit to produce the final sum and carry out.

For a 4-bit Ripple Carry Adder:

Best case: → no carry → minimal delay.

Worst case: → carry ripples through all 4 FAs → longest delay.

1. **Adder**: Value for delay = 122ps
2. **Decoder**: 39ps
3. **SRAM**: 29ps
4. **Sense Amplifier**: 5.7ps

Total System Delay: The cumulative delay for the critical path (Address → Decoder → Wordline → Bit line → Sense Amp Output) was measured to be approximately 170ps.

V. POWER CONSIDERATIONS

Power analysis was carried out to evaluate the energy consumption of each major block in the 32×32 SRAM read path.

The following values represent the average dynamic power under typical operating conditions:

1. **Adder**: 4.214uW
2. **Decoder**: 0.426uW
3. **SRAM**: 70.3mW
4. **Sense Amplifier**: 55.324uW

Total Read Power: The total power consumption during a read operation (Address → Adder → Decoder → Wordline Activation → Bitline Response → Sense Amplifier Output) was measured to be 71.758 mW.

VI. SIMULATION RESULTS

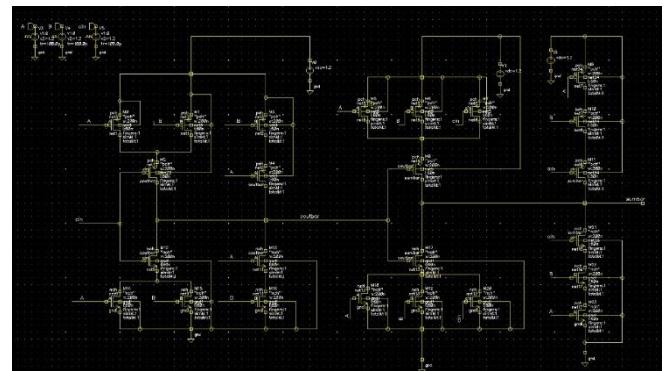


Figure: Mirror Adder

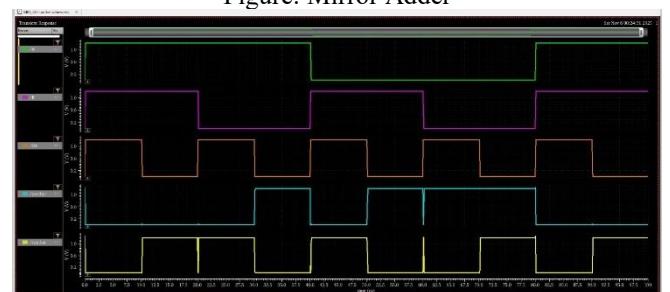


Figure: Result (Coutbar and Sumbar) for given A,B,Cin

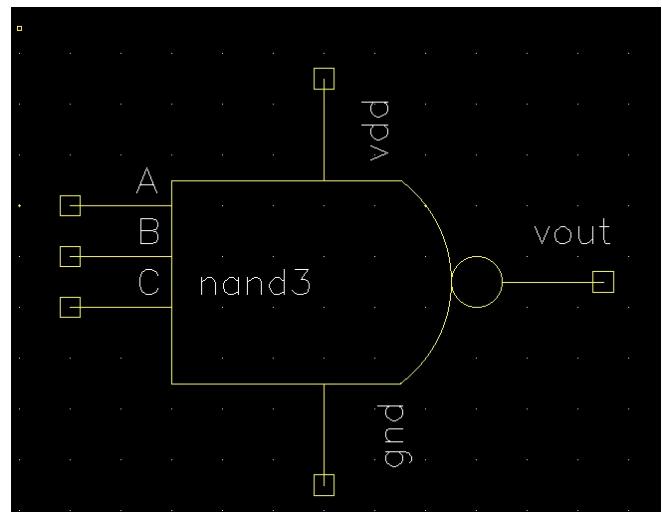
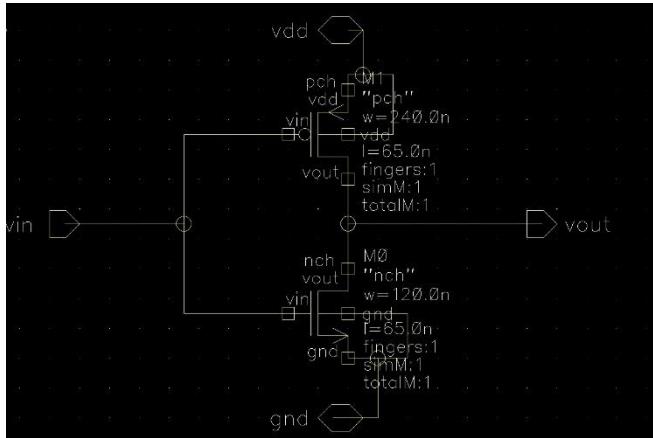


Figure: 3 input NAND

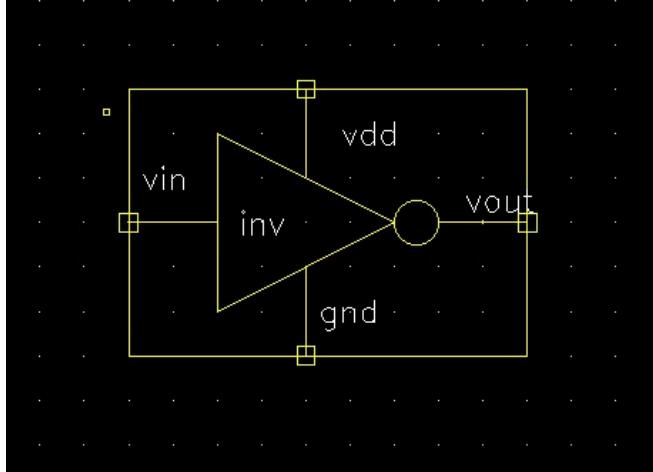


Figure: Inv Gate

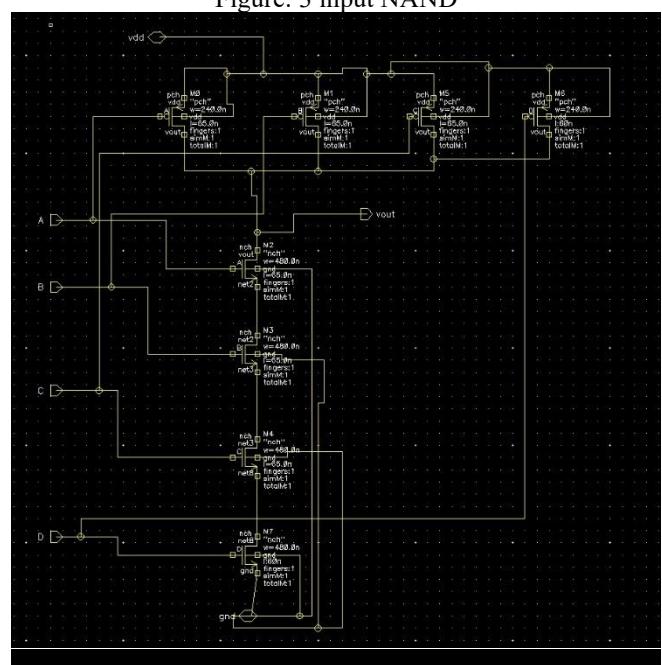
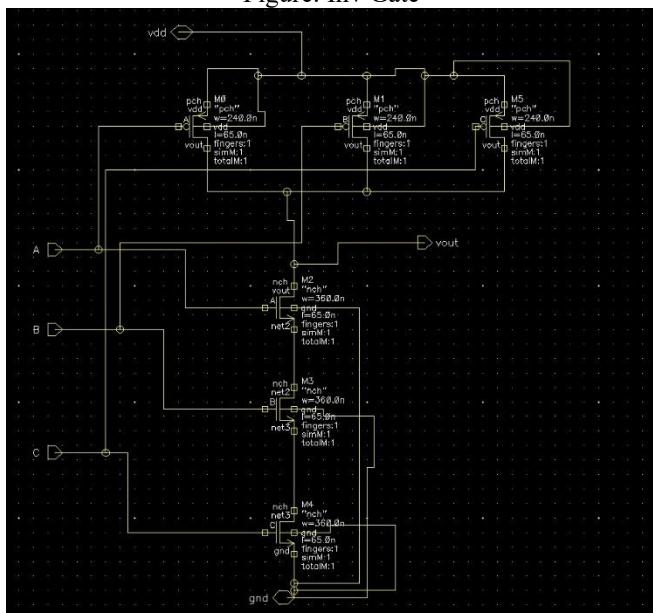


Figure: 4 Input NAND

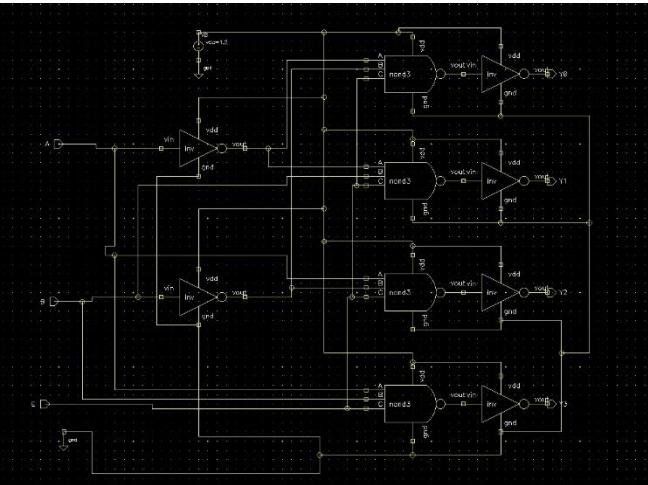


Figure: 2-4 Decoder

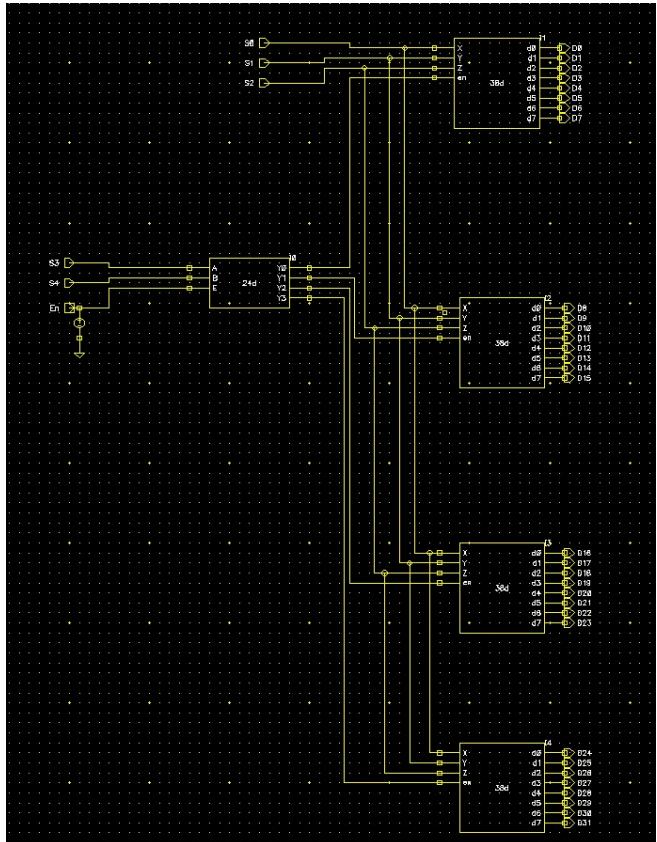


Figure: 5-32 Decoder

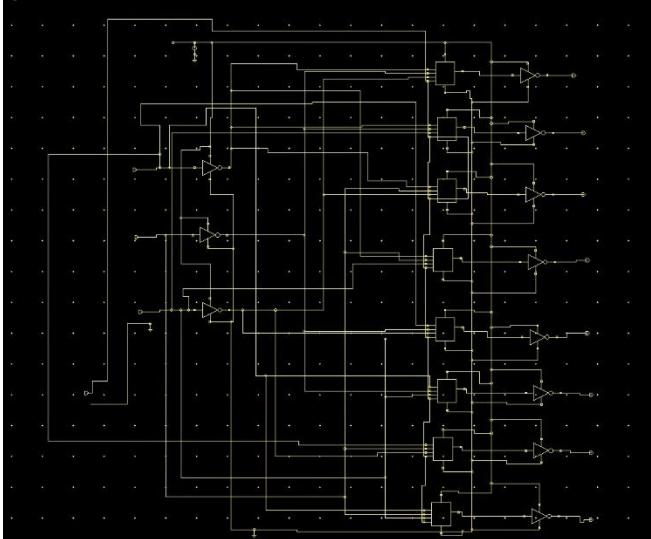


Figure: 3-8 Decoder

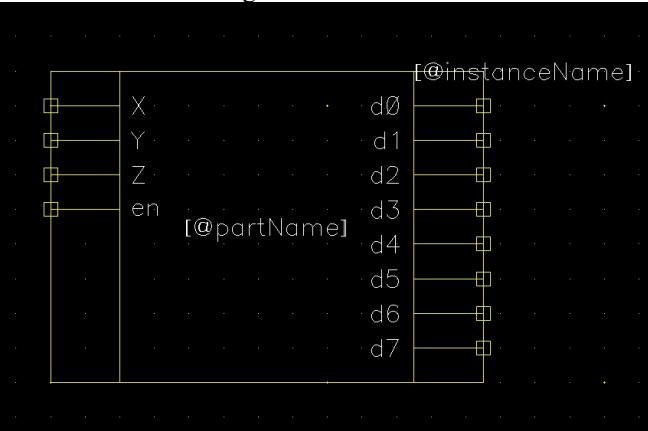


Figure: 3-8 Decoder

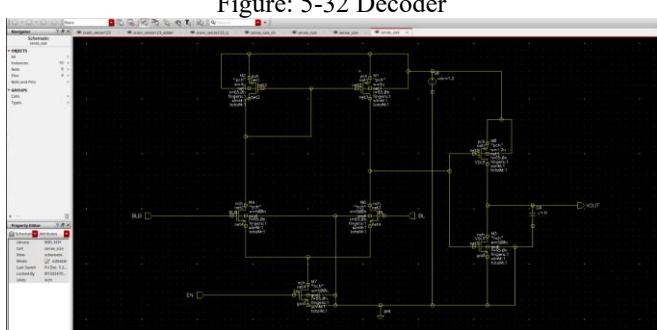


Figure: Sense Amplifier

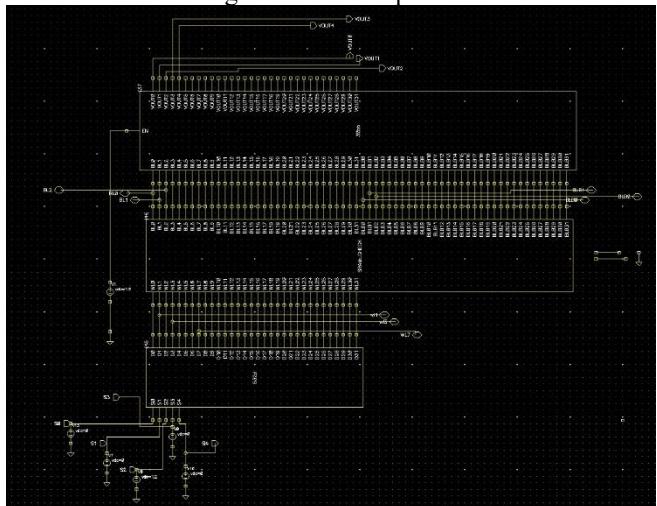


Figure: Decoder+SRAM+ SA

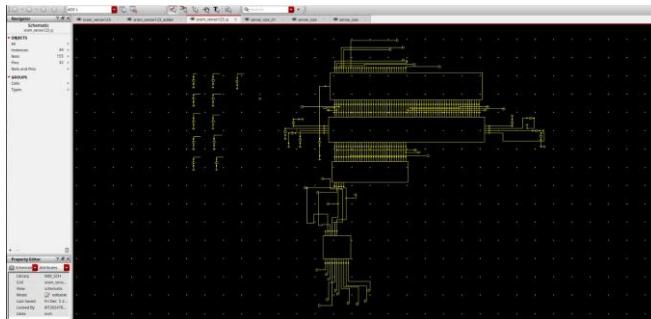


Figure: Final

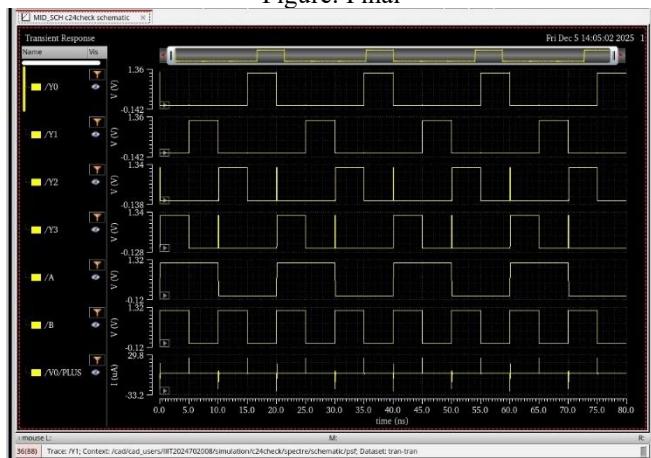


Figure: 2-4 Decoder Output

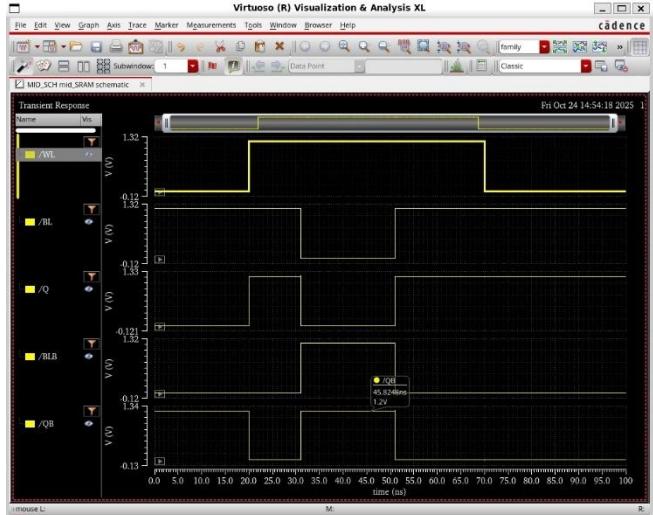
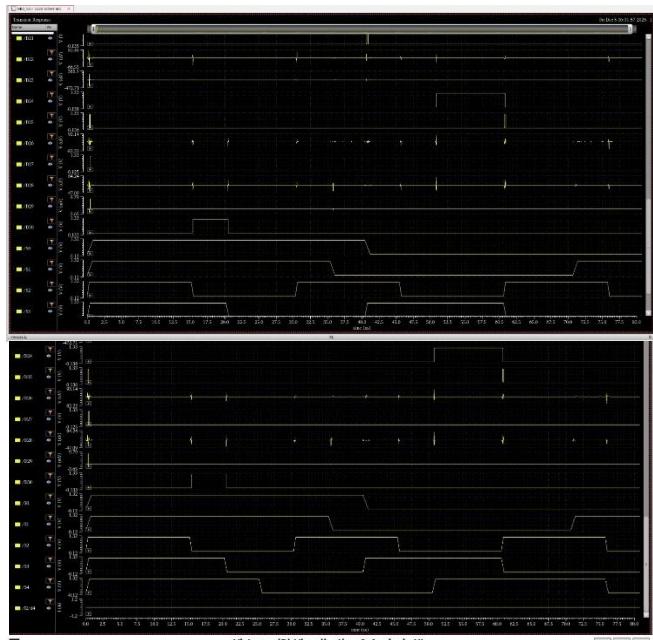
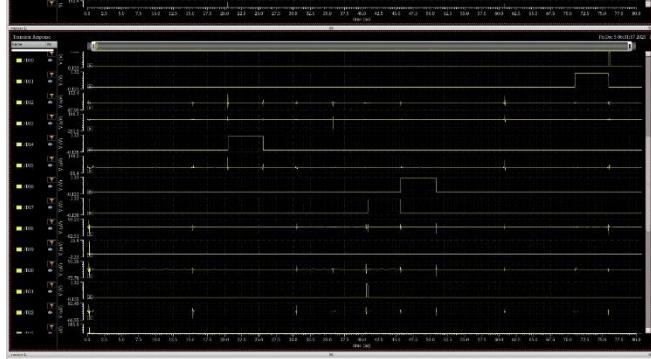
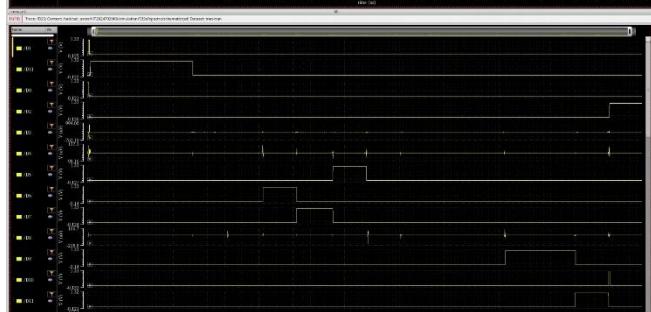
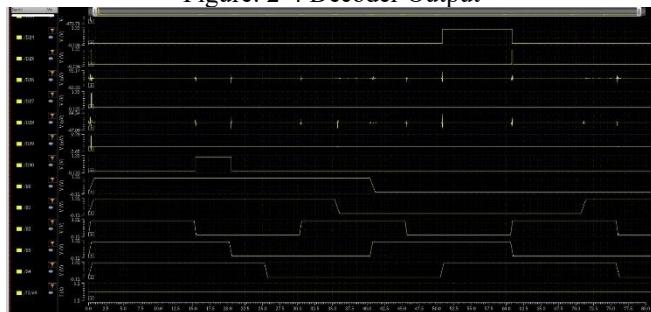


Figure: SRAM output

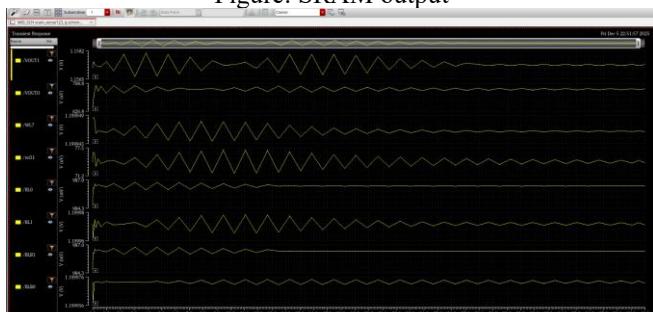


Figure: Sensory Amplifier output(Final Output)
Adder Input=00011 and 00100

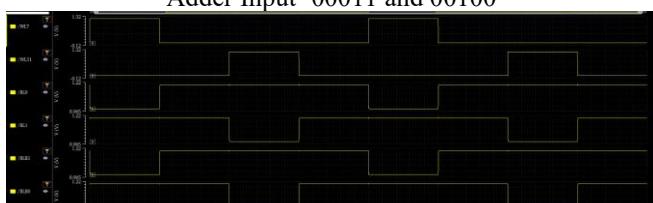


Figure: Back to Back Read
For WL31 and WL7
For WL31 Q0=1, WL7 Q0=0

VII. DESIGN OPTIMIZATIONS:

A. Trade-offs Introduced by Using a Mirror Adder Instead of a Conventional CMOS Adder

While the mirror adder improves speed and reduces transistor count, it also introduces several trade-offs:

- **Reduced Noise Margin:**

Because mirror adders rely on differential pull-up and pull-down paths, the switching thresholds are sharper but more susceptible to noise. This can slightly reduce robustness under supply or process variations.

- **Increased Design Complexity:**

The symmetric structure of a mirror adder requires careful transistor sizing to maintain balanced pull-up and pull-down strengths. This increases layout and sizing complexity compared to a standard CMOS adder.

- **Potential Leakage Issues:**

Since the mirror structure keeps more internal nodes floating or partially charged, leakage currents may be higher under low-power conditions.

- **Driving Capability Constraints:**

Mirror adders typically generate weaker output drive compared to full CMOS logic unless buffers are added, which may add slight overhead if strong drive strength is needed.

B. Trade-offs Introduced by Using a High-Speed Voltage-Difference Sense Amplifier

High-speed sense amplifiers greatly improve read time but bring their own trade-offs:

- **Lower Noise Margin / Higher Sensitivity to Mismatch:**

Because the amplifier is designed to detect very small voltage differences quickly, it becomes more sensitive to device mismatch, supply noise, and bitline disturbances. This can reduce read stability in worst-case corners.

- **Higher Design and Control Complexity:**

High-speed sense amplifiers require precise timing of enabling signals and careful precharge control. The added control circuitry slightly increases overall design complexity.

- **Area Overhead for Additional Biasing or Latch Structures:**

Some high-speed sense amplifier topologies (e.g.,

latch-type, current-mode) require extra transistors or bias circuits, consuming more area compared to simple resistive or differential amplifiers.

- **Possibility of Increased Power Consumption:**

To achieve faster sensing, the amplifier may momentarily draw higher dynamic power during activation, even though total energy per operation may remain low.

VIII. CONCLUSION

The implemented **32×32 SRAM module** integrates all key functional blocks including the adder, decoder, memory cell array, and sense amplifier to deliver efficient and reliable read operations. The architecture offers:

- **Compact Layout:** The 32×32 array provides a total storage capacity of 1024 bits while keeping the read circuitry straightforward and efficient.
- **Precise Address Decoding:** The decoder accurately selects the intended memory location corresponding to the applied address.
- **High-Speed Data Retrieval:** The sense amplifier ensures fast and dependable detection of small voltage differences on the bitlines during read operations.
- **Seamless Block Integration:** Incorporating an adder enhances address handling flexibility and contributes to more efficient memory access control.

The **overall power consumption** of the complete SRAM system is **130mW**.

This design is well-suited for applications demanding high-speed, dependable read-only memory access, such as cache arrays and lookup-table implementations in embedded systems.

IX. CONTRIBUTIONS

All members contributed equally to the design, simulation, and documentation of the project. Responsibilities such as SRAM cell design, logic gate implementation, adder and decoder development, system integration, simulation setup, and report writing were collaboratively carried out by all of us equally.